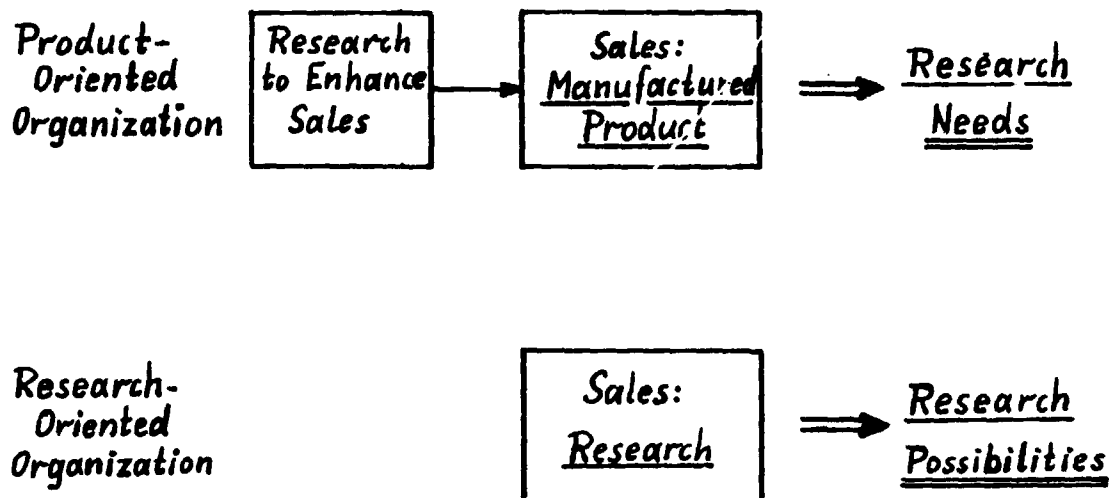


RESEARCH POSSIBILITIES? NO! Needs for Research to Make PV Solar Energy Utilization Broadly Competitive

UNIVERSITY OF PENNSYLVANIA

M. Wolf ✓

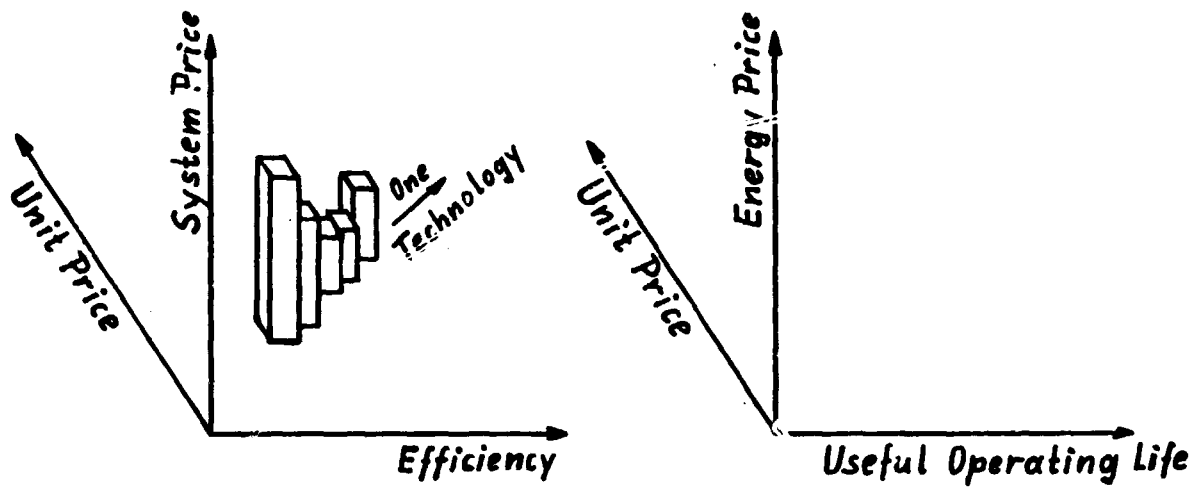
Two Types of Research Philosophies



MAJOR CRITERION
FOR
COMPETITIVENESS:
PRICE OF ELECTRIC ENERGY

PLENARY SESSION: M. WOLF

Multivariable Relationships



The Subsystems

- MODULE →
- LIGHT PROCESSOR (CONCENTRATOR, TRACKER)
 - CONVERTER ARRAY
 - POWER CONDITIONING
 - ENERGY STORAGE
 - CONTROL. PROTECTION
 - AUXILIARY ENERGY

System Characteristics Determine Market

| SYSTEM TYPE | LIKELY USE | MARKET SIZE | MOST LIKELY CANDIDATES |
|--|---|-------------|--|
| HIGH CONCENTRATION, TRACKING VERY HIGH EFFICIENCY CONVERTER | ARID CLIMATES, CENTRAL STATION (ATTENDED OPERATION) | LIMITED | SINGLE CRYSTAL $Al_xGa_{1-x}As$ / GaAs (SINGLE CRYSTAL Si?) MULTI-BANDGAP SYSTEMS |
| FLAT-PLATE, HIGH EFFICIENCY LONG LIFE | ALL USES, COMMERCIAL INSTALLATION | LARGEST | SINGLE CRYSTAL Si (MULTI-BANDGAP SYSTEMS?) |
| VERY LOW COST, LOW EFFICIENCY LIMITED LIFE | PRIMARILY RESIDENTIAL, DO-IT-YOURSELF INSTALLATION | LIMITED | THIN-FILM a-Si OTHER THIN FILM SEMICONDUCT. (Cu_2InSe/CdS ?) |

Research Needs on BOS

| SUBSYSTEM | NEEDED ATTRIBUTES | PAYOFF | RISK | TIME RANGE TO ATTAINMENT |
|----------------------------|---|---------|------|--------------------------|
| POWER CONDITIONING | LOW PRICE, HIGH EFFICIENCY | I | L | S TO I |
| CONTROL, PROTECTION | LOW PRICE, SIMPLE | I | L | S |
| ENERGY STORAGE | LOW PRICE LONG LIFE HIGH EFFICIENCY HIGH DISCHARGE RATE DEEP CYCLE CAPABILITY | VH | H | L |
| FIELD INSTALLATION | LOW PRICE | VH | VH | ? |
| HIGH-RATIO CONCENTRATOR | LOW PRICE LOW MAINTENANCE | I | H | I |
| AUXILIARY ENERGY | LOW PRICE | H TO VH | VH | L |

S = SMALL OR SHORT
I = INTERMEDIATE

H = HIGH
VH = VERY HIGH

L = LONG
RISK = INVERSE PROBABILITY FOR
ATTAINMENT OF EXPECTED PAYOFF

Research Needs on Modules

| ITEM | NEEDED ATTRIBUTES | PAYOFF | RISK | TIME TO ATTAINMENT |
|------------------------|--|--------|---------|--------------------|
| CELL (MANUF'G PROCESS) | COST REDUCTION 10-20 TIMES | VH | I | S TO I |
| CELL | EFFICIENCY INCREASE 25 TO 66% SINGLE CELLS TO 300% MULTI-BANDGAP SYSTEMS (WILL REQUIRE MODIFIED CELL PROCESSING) | VH | I VH | S TO I L |
| MODULE | ≥ 20 YEAR LIFE COST REDUCTION } COMPATIBLE? | VH | I | I TO L |

Current Status of Major Module Processes

| TECHNOLOGY AREA | APPROACH | EXPECTED RESULTS | STATUS |
|-------------------------------|--|--|--|
| <u>SILICON SOLAR/MODULES:</u> | | | |
| LOW COST PURIFICATION | SiH ₄ PROCESS | ~\$14.-/KG SEMICONDUCTOR- GRADE SI | PRIVATE INDUSTRY (UNION CARBIDE) GOES INTO PILOT PLANT OPERATION. |
| | Si H ₂ Cl ₂ PROCESS | ~\$25.-/KG SEMICONDUCTOR GRADE SI | PRIVATE INDUSTRY (HEMLOCK SEMICONDUCTOR CONVERTS EXISTING SiHCl ₃ PLANT |
| SHEET GENERATION | (SEMI-) CONTINUOUS AUTOMATED Cz X-TAL GROWTH | 150KG/CRUCIBLE, 15 CM DIA | NEARLY PRODUCTION READY BOTTLENECK: SLICING |
| | SEMICRYSTAL SI | LOWER COST THAN Cz, COMPARABLE PERFORMANCE | PRODUCTION COST/PERFORMANCE EXPERIENCE NEEDED. BOTTLENECK: SLICING |
| | SLICING | HIGH THROUGHPUT, LOW KERF, LOW COST | LITTLE ADVANCEMENT. <u>PROBLEM AREA.</u> |
| | RIBBON GROWTH: EFG | LOW COST, Cz COMPATIBLE CELL PERFORMANCE | PILOT PRODUCTION CELL EFFICIENCY STILL TOO LOW |

PLENARY SESSION: M. WOLF

| TECHNOLOGY AREA | APPROACH | EXPECTED RESULTS | STATUS |
|--|---|--|---|
| | WEB-DENDRITE | LOW COST, CZ COMPATIBLE CELL PERFORMANCE | CZ COMPATIBLE EFFICIENCY PROVEN. ONLY MATERIAL WITH INTERNAL GETTERING. PRE-PILOT STAGE. PRODUCTION COST EXPERIENCE NEEDED. WILL PRIVATE INDUSTRY GO AHEAD? |
| CELL FABRICATION: | PROCESS SIMPLIFI- CATION, BY-PRODUCT REDUCTION, AUTOMA- TION | \$0.5 TO 1.5/W _p MODULES OF 14-17% EFFICIENCY | CONSIDERABLE TECHNOLOGY ADVANCE- MENTS MADE. ~\$10/W _p AT 7-12% EFFICIENCY. CONTINUED SLOW PROGRESS IN PRIVATE INDUSTRY. STAGNATION AT A PRICE LEVEL OF 5-10\$/W _p AHEAD? |
| MODULE ASSEMBLY | BETTER MATERIAL SELECTION, AUTOMA- TION | DTO 20-YEAR LIFE | DTO COST/LIFE TRADE-OFF UNCERTAIN. |
| <u>A Si</u> | THIN FILM PROCESSES, LOW-COST ENCAPSULA- TION | < \$0.5/W _p LIMITED EFFI- CIENCY | RESEARCH STAGE. PRODUCTION IN JAPAN FOR CALCU- LATOR/WATCH MARKET |
| <u>AL_xGA_{1-x}As/GAAs</u> | SINGLE X-TAL CELLS. | HIGHER EFFICIENCY THAN Si CELLS, SUPERIOR HIGH TEMPERATURE PER- FORMANCE, BETTER RADIATION RESIS- TANCE FOR SPACE CELLS | PILOT LINE QUANTITIES AVAILABLE PRIMARILY CONCENTRATOR AND SPACE CELLS. MAY FORM COMPONENT IN MULTI- BANDGAP SYSTEM |
| Cu ₂ S/CdS CELLS | THIN FILM PROCESSES, LOW-COST ENCAPSULA- TION | < \$0.5/W _p . LIMITED EFFI- CIENCY, LIFE | TECHNOLOGY BEING ABANDONED? |
| Cu ₂ InSe/CdS CELLS | DTO | HIGHER EFFICIENCY, LONGER LIFE THAN Cu ₂ S/CdS | RESEARCH STAGE, MAY FORM COMPONENT IN MULTI-BANDGAP SYSTEM. |
| ALL OTHER COM- POUND SEMICON- DUCTORS | MOSTLY THIN FILM PROCESSES | MOSTLY LOW COST | VARIOUS LEVELS OF RESEARCH. LIKELY REDUNDANT WITH FURTHER ADVANCED APPROACHES. SOME CANDIDATES FOR MULTI- BANDGAP SYSTEMS. |

Who Pays What Research?

| SHORT RANGE, LOW RISK | IN BETWEEN | LONG RANGE, HIGH RISK GOVERNMENT |
|--|--|---|
| <u>MANUFACTURING INDUSTRY</u> | <u>MANUFACTURING INDUSTRY</u> | <u>GOVERNMENT</u> |
| GRADUAL PROCESS ADVANCEMENT, AUTOMATION FOR COST REDUCTION. | SOME THIN FILM APPROACHES (HOW LONG, IF MARKET DOES NOT DEVELOP SOON?) | SI-CELLS: EFFICIENCY >20% (AM1) |
| SMALL STEPS TO EFFICIENCY IMPROVEMENT, EXTENSION OF OPERATING LIFE | <u>?WHO?</u> | MULTI-BANDGAP SYSTEMS GRAIN BOUNDARY RESEARCH THIN FILM DEVICES (?) BATTERIES/FUEL CELLS |
| GRADUAL POWER CONDITIONING PROGRESS | RADICAL PROCESS ADVANCEMENT RELIABILITY DEVELOPMENT STANDARDIZATION CONCENTRATORS FIELD INSTALLATION | <u>MANUFACTURING INDUSTRY</u> A-SI APPROACHES |

Identifiable Research Needs for Efficiency Improvement

SINGLE CRYSTAL SI CELLS

| GOAL | NEEDED UNDERSTANDING | FURTHER ACTIONS |
|--|---|---|
| LONGER MINORITY CARRIER LIFETIME Si | CRYSTAL STRUCTURE, ROLE OF IMPURITIES (HEAVY METALS?) ROLE OF COMPLEXES (O ₂ , C, STRUCTURE DEFECTS?) ORIGIN OF DEFECTS, IMPURITIES INTRODUCTION MECHANISM OF DEFECTS, IMPURITIES POTENTIAL AND LIMITS OF GETTERING INFLUENCE OF POST-GROWTH HEATING, LIGHT | PROCESS CONTROL IN CRYSTAL (RIBBON) GROWTH PROPER POST-GROWTH PROCESS SELECTION |

| GOAL | NEEDED UNDERSTANDING | FURTHER ACTIONS |
|--|--|--------------------------|
| <u>SINGLE CRYSTAL SI CELLS, CONTINUED</u> | | |
| SURFACE PASSIVATION | EXACT MECHANISM REQUIREMENTS ON PASSIV- ATION LAYERS WAYS TO MEET REQUIREMENTS OPTICAL PROPERTIES OF PASSIVATION LAYERS INTERACTIONS WITH AR COATINGS | PROCESS DEVELOP- MENT |
| ATTAINMENT OF PRE- DESIGNED DEVICE STRUCTURE | EFFECTS RESULTING FROM INDIVIDUAL PROCESSES (DIFFUSION, CVD OR LPE EPI, ETC) "LOW TEMPERATURE" PRO- CESSING FEASIBLE? LIFETIME MAINTENANCE THROUGHOUT PROCESSES? OR RECOVERY? SIMPLER PROCESS METHODS? | |
| "CLOSED LOOP DESIGN" | ANALYSIS: ALL PARAMETERS WHICH INFLUENCE PERFORMANCE OR ENTER MODELLING LACKING: RELIABLE MEASUREMENTS OF FRONT LAYER DIFFUSION LENGTH; MEASUREMENT OF: DIFFUSION LENGTH OF MORE HEAVILY DOPED LAYERS; EFFECTIVENESS OF HIGH/LOW JUNCTIONS; FRONT SURFACE RECOMBINATION VELOCITY. TWO METHODS BASED ON COM- PLETELY DIFFERENT EFFECTS SHOULD BE AVAILABLE FOR COR- ROBORATION OF RESULTS. UNDERSTANDING OF HEAVY-DOPING EFFECTS TO ALLOW MORE PRECISE MODELLING, ASCERTAIN ULTI- MATELY ACHIEVABLE EFFICIENCY. | |

POLYCRYSTAL DEVICES

ALL THE ABOVE, PLUS:
EFFECTS OF GRAIN BOUNDARIES
ON DEVICE PERFORMANCE;
CONTROL OF ELECTRICAL EFFECTS
OF GRAIN BOUNDARIES
DEVICE DESIGN TO MINIMIZE
EFFECTS OF GRAIN BOUNDARIES

| GOAL | NEEDED UNDERSTANDING | FURTHER ACTIONS |
|------|---|-----------------|
| | <u>COMPOUND SEMICONDUCTORS</u> (INCL. AMORPHOUS Si:H, ETC) | |
| | ALL OF ABOVE, EXCEPT FOR GRAIN BOUNDARIES, WHERE NOT APPLICABLE. PLUS: LEVEL OF EXISTING KNOWL- EDGE GENERALLY MUCH LOWER THAN FOR Si EFFECTS OF STOICHIOMETRY DEVI- ATIONS. CONTROL OF FABRICATION PROCESSES. | |

MULTI-BANDGAP SYSTEMS

ALL OF ABOVE; EXCEPT FOR
 GRAIN BOUNDARY EFFECTS, WHERE
 NOT APPLICABLE. PLUS:
 INTERFACES BETWEEN CELLS OF
 DIFFERENT BANDGAP (TUNNEL-
 JUNCTIONS?)
 PROBLEMS OF MISMATCH BETWEEN
 CELLS UNDER DIFFERING INTENSITY,
 SPECTRAL DISTRIBUTION (AM),
 TEMPERATURE.

The Technology Race

